

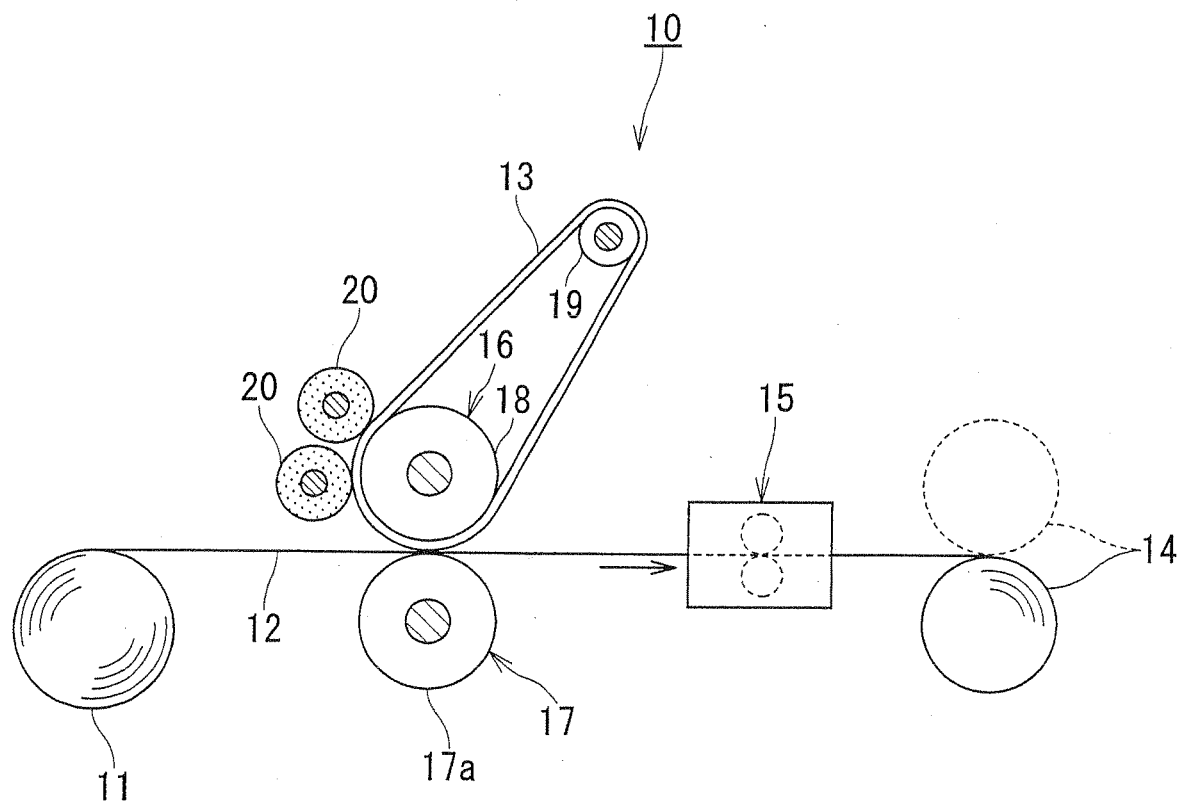
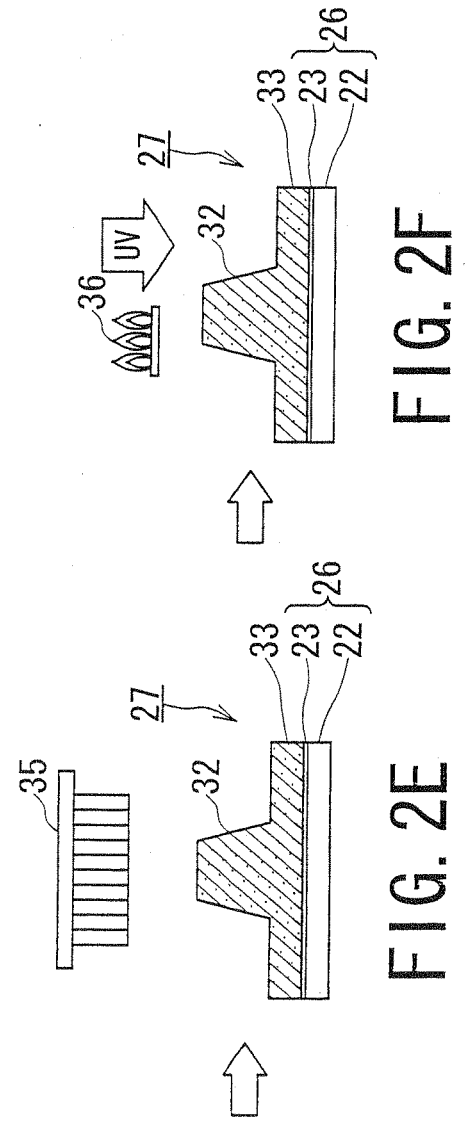
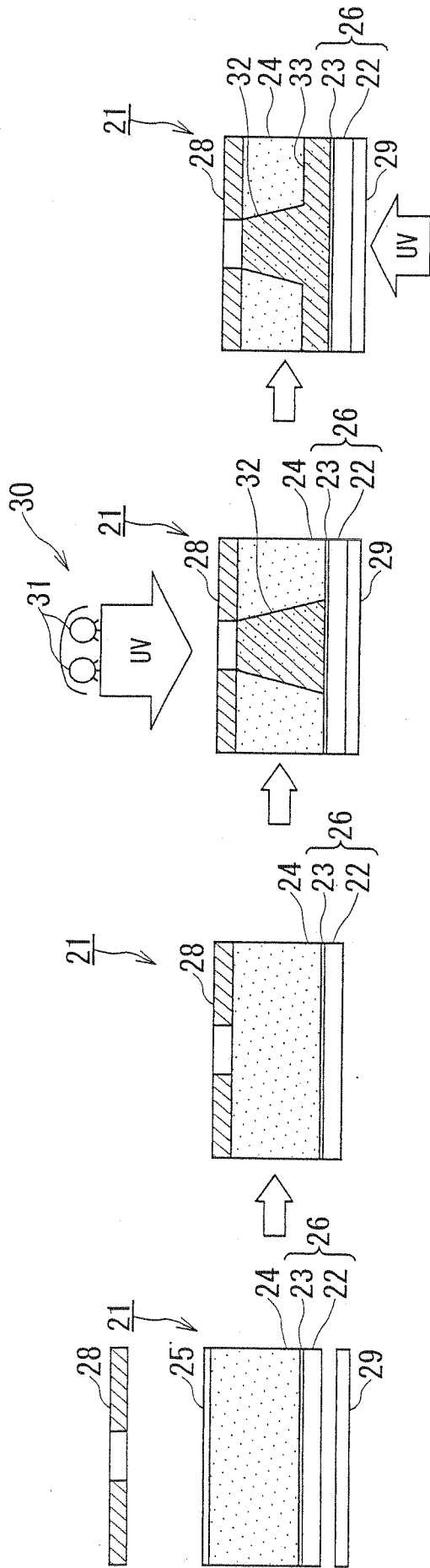


FIG. 1



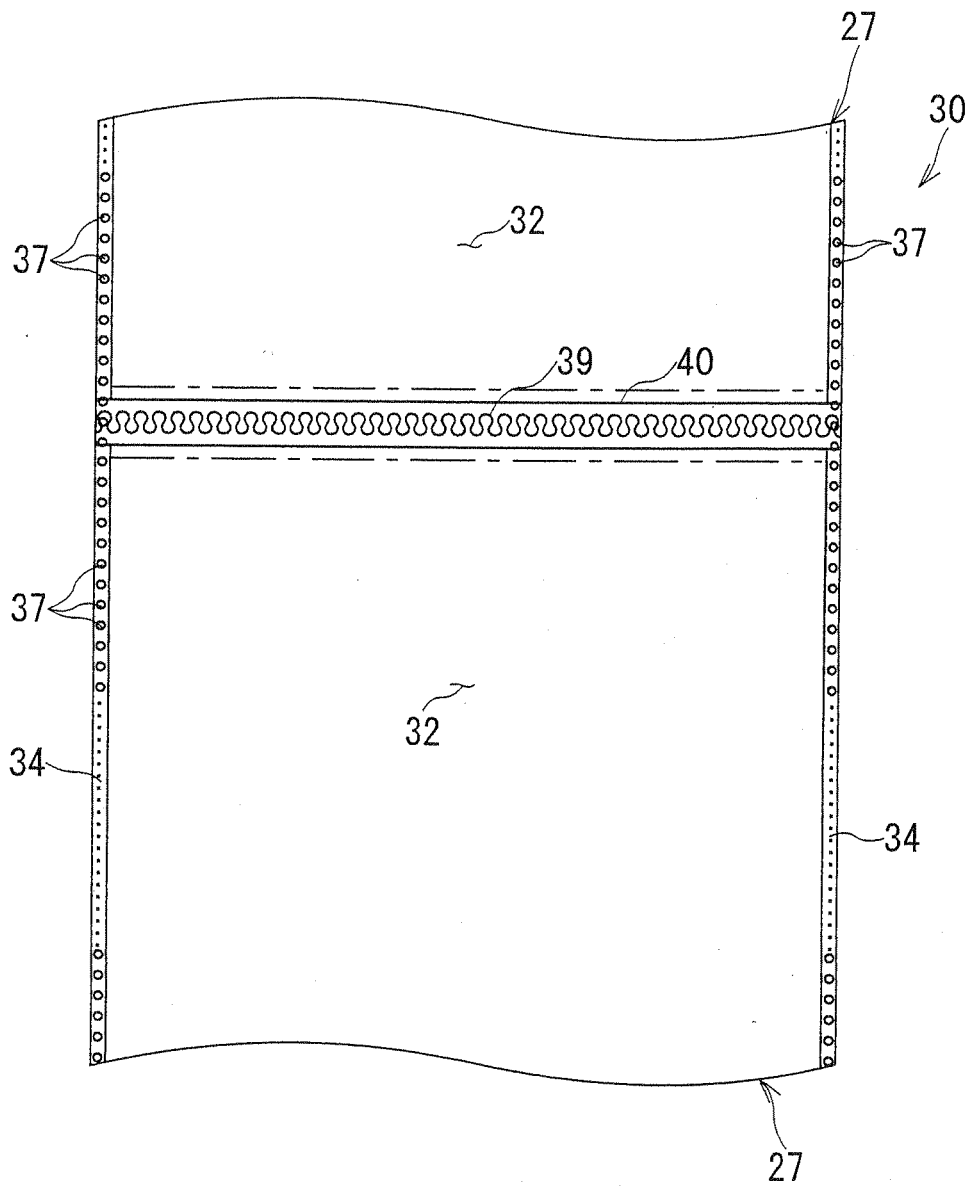


FIG. 3

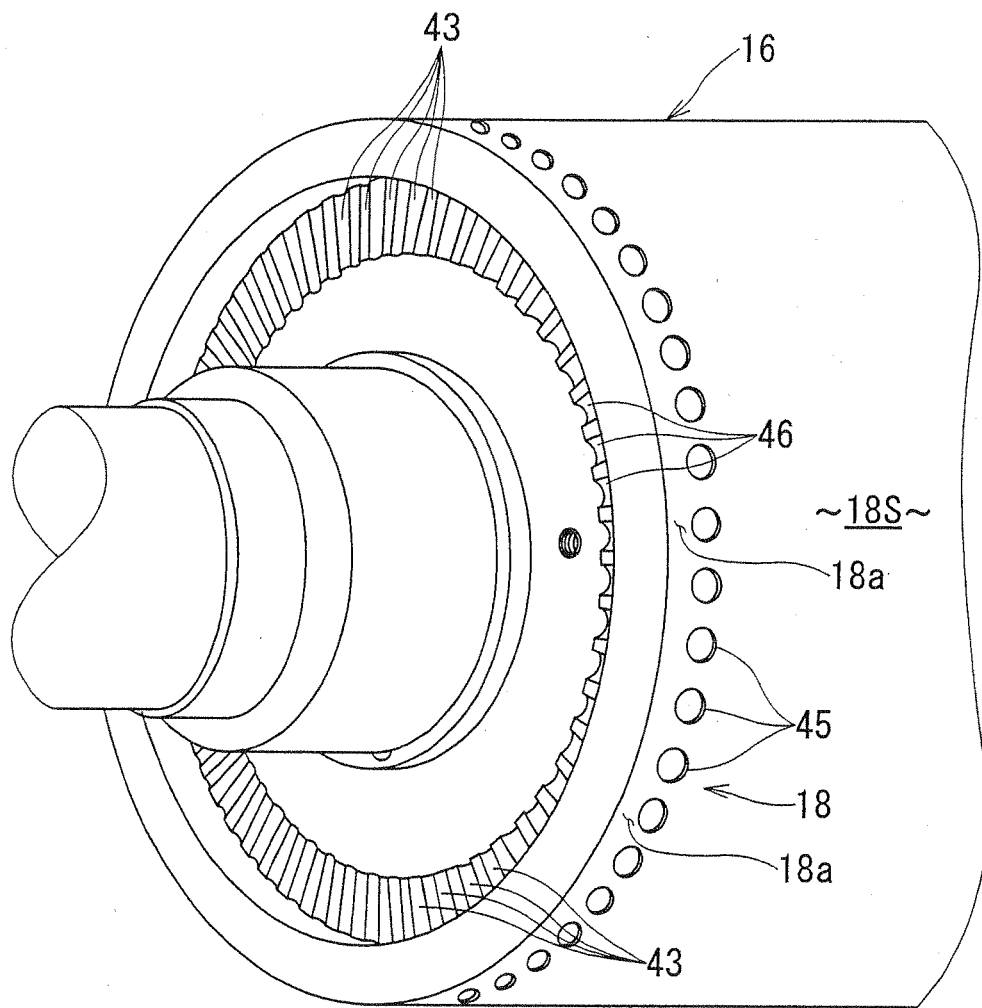


FIG. 4

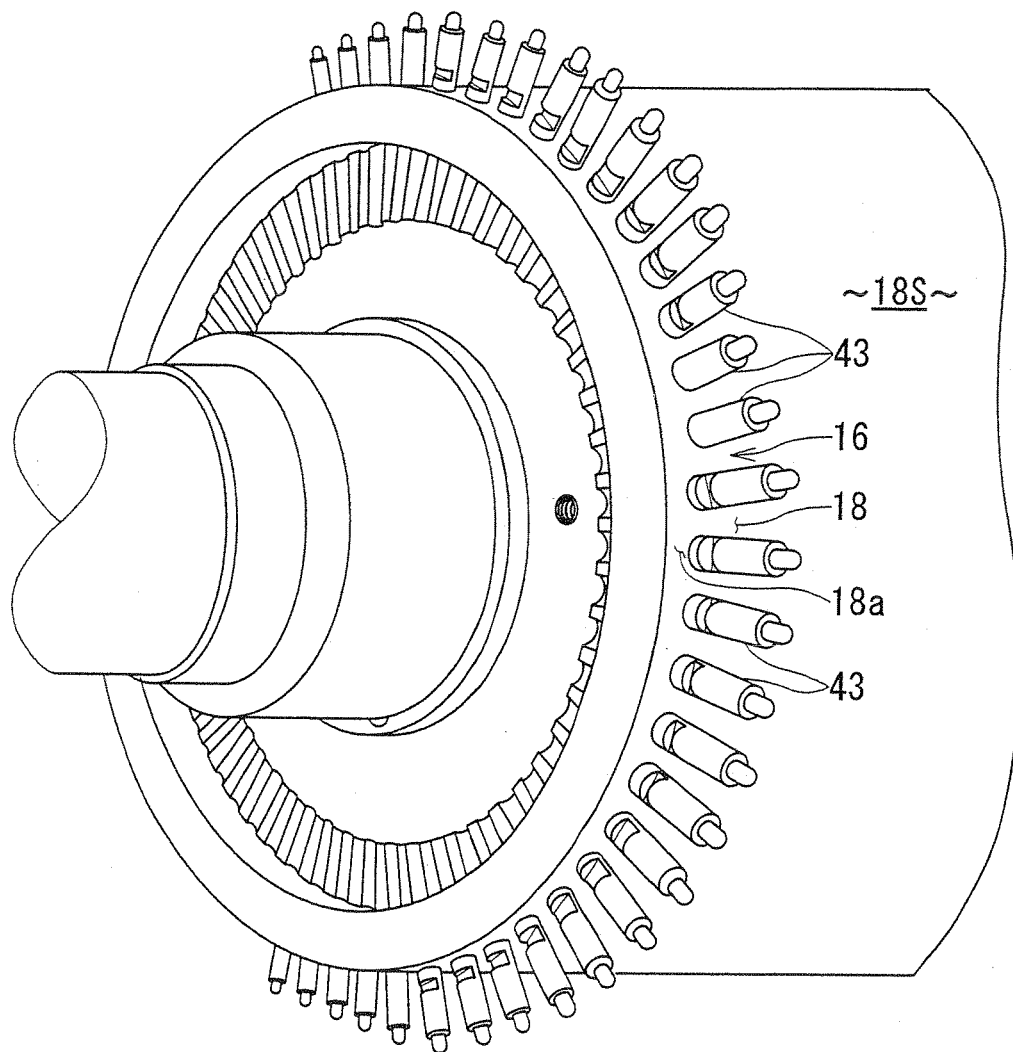


FIG. 5

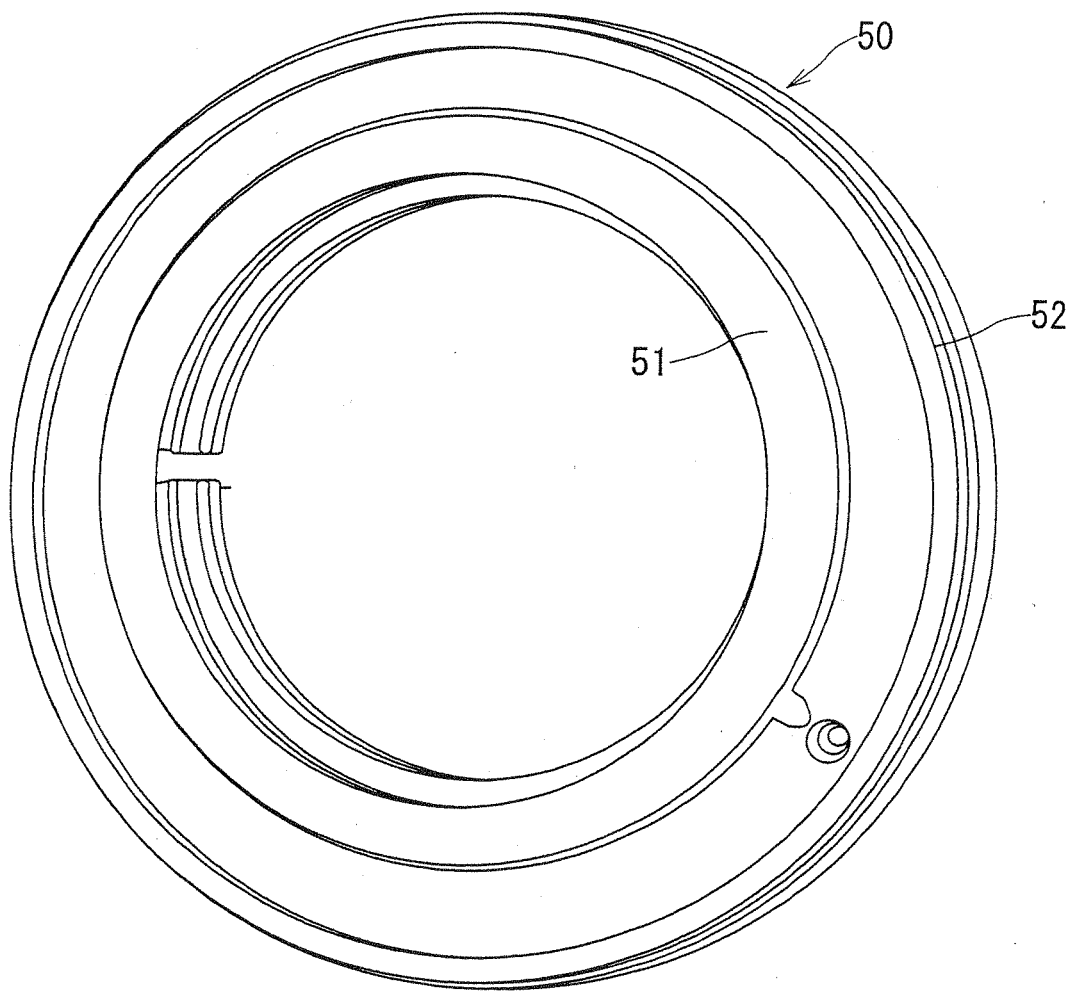


FIG. 6

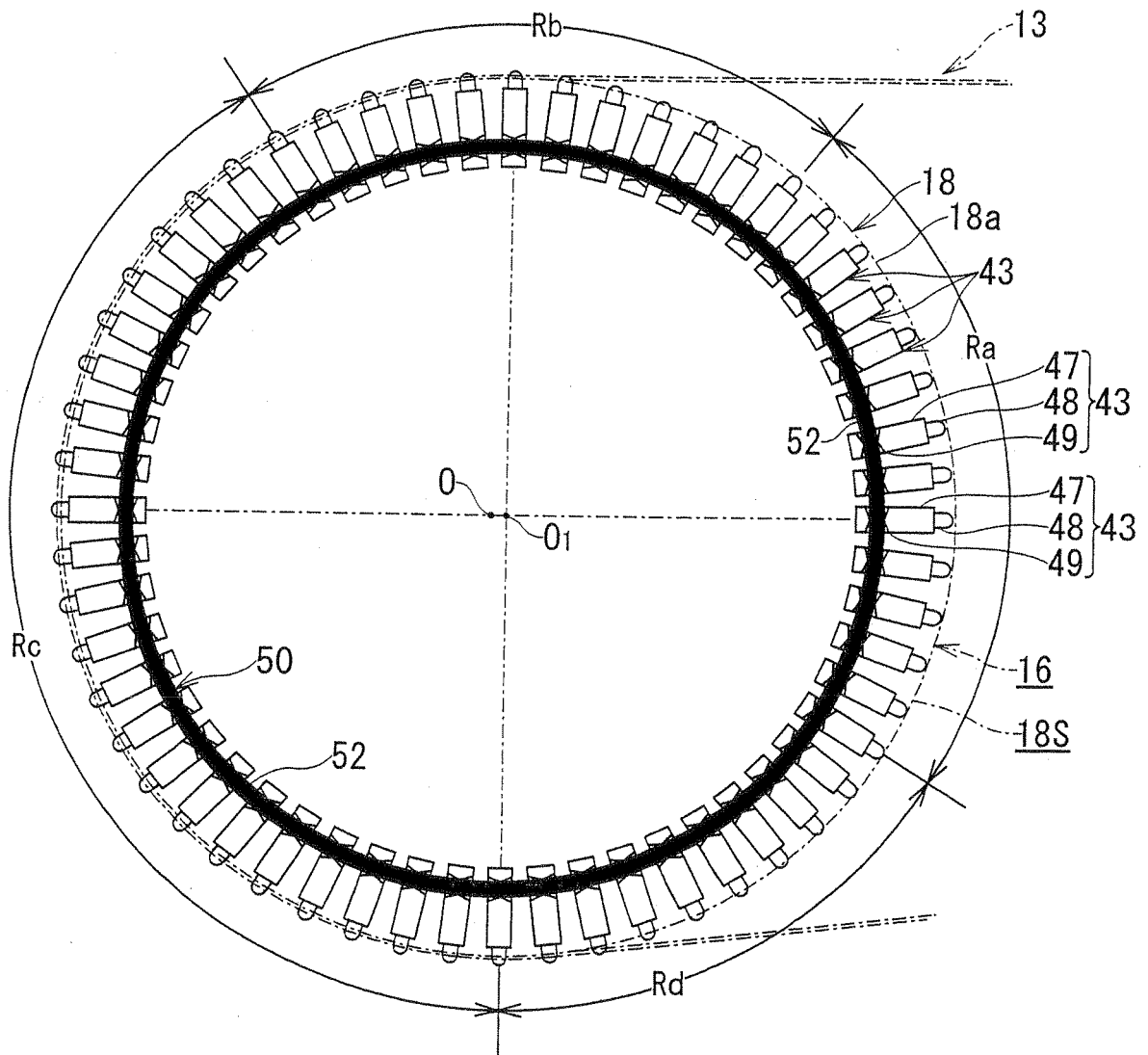


FIG. 7

FIG. 8A

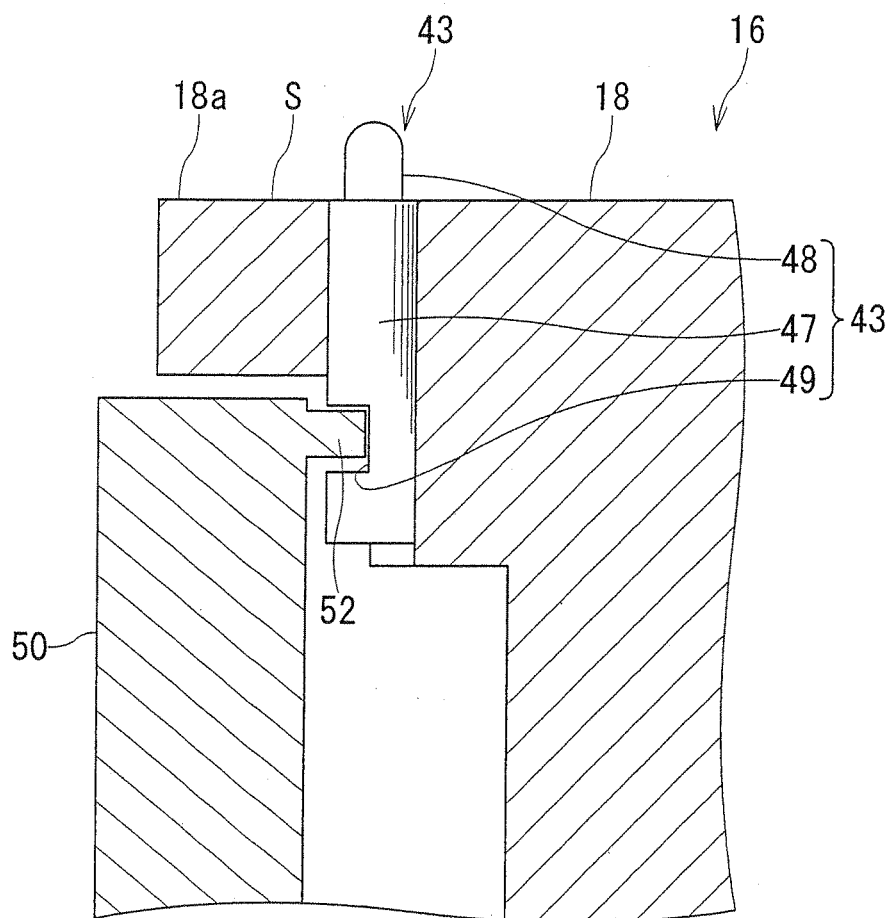
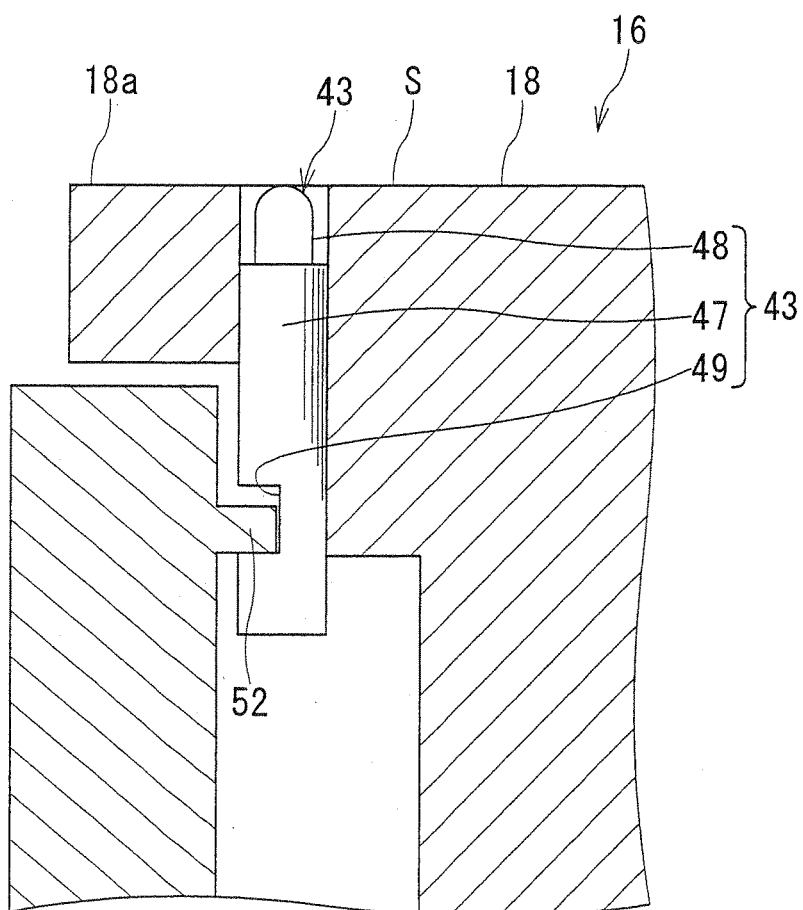


FIG. 8B



EXPERIMENTAL DATA OBTAINED BY VARYING BACK EXPOSURE QUANTITY

FIG. 9B

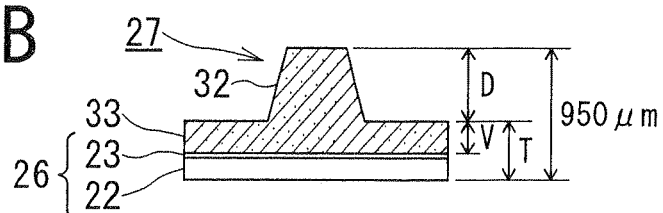


FIG. 9A

	AVERAGE EXPOSURE (mJ/cm ²)	TOTAL BASE THICKNESS T (μm)	RESIDUAL RESIN V (BACK DEPOSIT LAYER) (μm)	RELIEF DEPTH D (μm)
RELIEF EXPOSURE	520.1	—	—	—
COMP. EX. 1	12.8	220	0	730
COMP. EX. 2	17.8	220	0	730
COMP. EX. 3	19.8	220	0	730
COMP. EX. 4	22.2	220	0	730
COMP. EX. 5	24.7	220	0	730
COMP. EX. 6	29.7	320	100	630
EX. 1	34.6	460	240	490
EX. 2	44.9	570	350	380
EX. 3	47.0	600	380	350
EX. 4	49.9	620	400	330
EX. 5	52.0	640	420	310
EX. 6	52.3	660	440	290
EX. 7	54.3	680	460	270
EX. 8	61.1	690	470	260
EX. 9	64.3	700	480	250
EX. 10	66.3	730	510	220
EX. 11	68.2	760	540	190
EX. 12	68.8	780	560	170
EX. 13	71.7	820	600	130
COMP. EX. 7	73.9	850	630	100
COMP. EX. 8	82.3	880	660	70
COMP. EX. 9	—	910	690	40

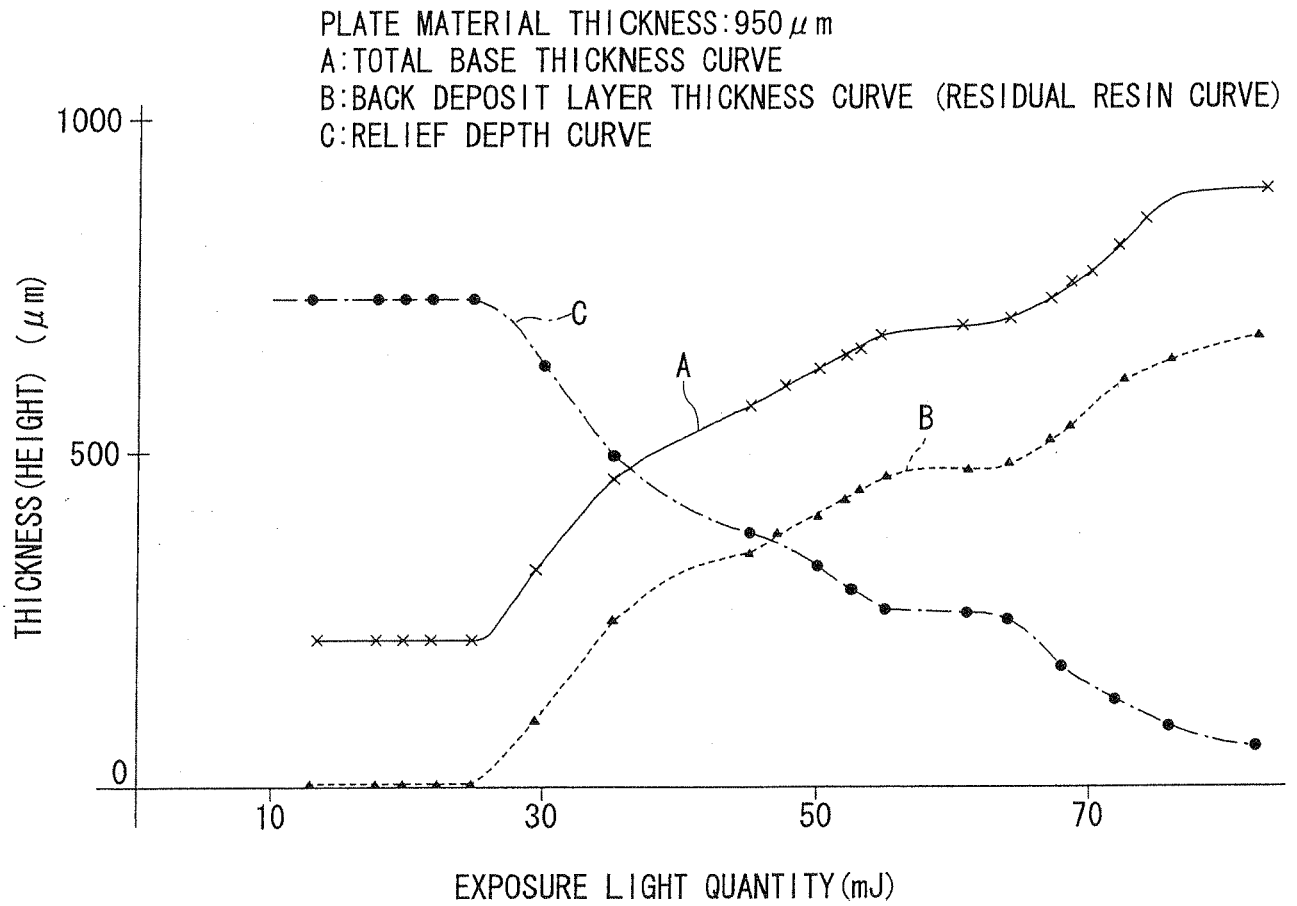
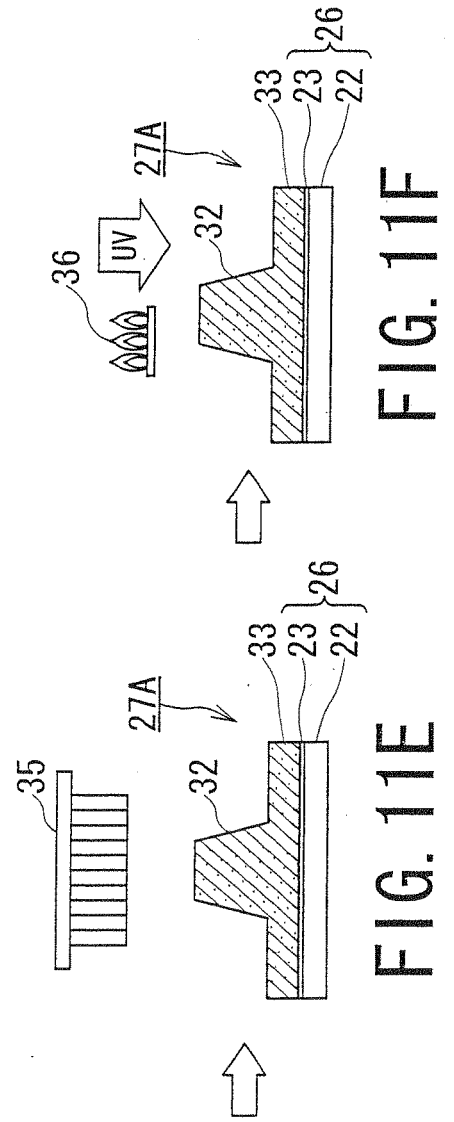
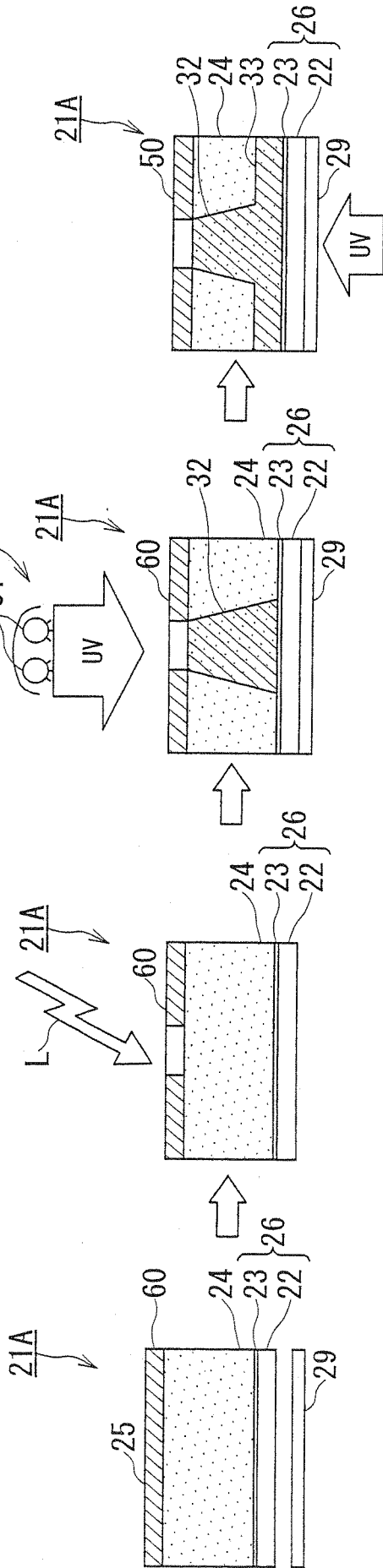


FIG. 10



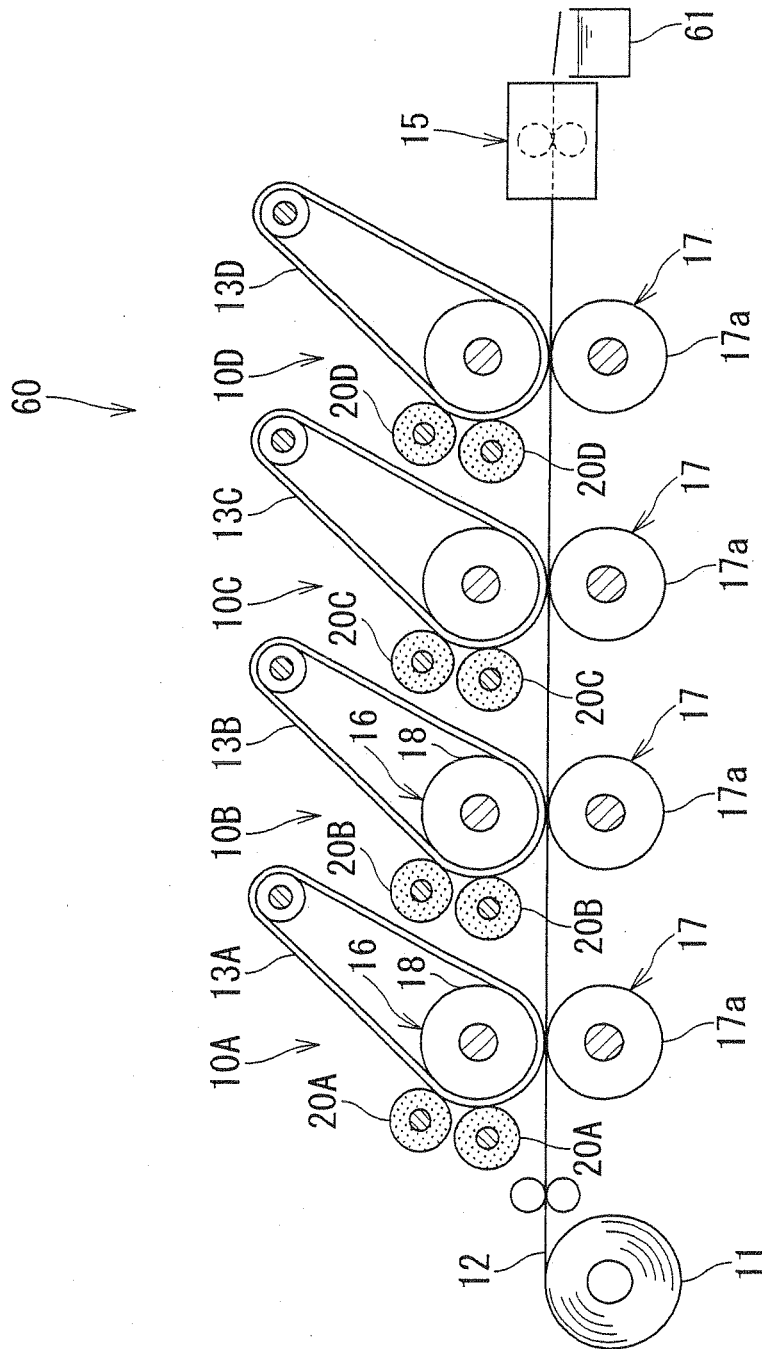


FIG. 12